

FORM PTO-1449 U.S. Department of Commerce Patent and Trademark Office					Attorney, Docket Number 5576-137			Serial No. to be assigned
LIST OF DOCUMENTS CITED BY APPLICANT								87 87
(Use several sheets if necessary)					Applicants: Satoshi Watanabe			5 n . 8
								Group
					Filing Date concurrently herewith			1752
U. S. PATENT DOCUMENTS								
Examiner `Initial		Document Number	Date	Name		Class	Subclass	Filing Date if Appropriate
40		5,569,784	10/29/96	Watanabe et al.		564	430	
yct		5,580,695	12/03/96	Murata et al.		430	270.1	
GCT	-	5,972,559	10/26/99	Watanabe et al.		430	270.1	
)		6,150,068	11/21/00	Sato et al.		430	270.1	
FOREIGN PATENT DOCUMENTS								
Document					DOCOMENTS	<u> </u>		Translation
	:	Number	Date	Country		Class	Subclass	Yes   No
ycr		5249683	09/28/93	Japan		G03F	007/075	X (abstract)
yct		10048814 A	02/20/98	Japan		G03F	007/004	X (abstract)
yct		10073912	03/17/98	Japan		G03F	001/00	X (abstract)
yct		10133371	05/22/98	Japan		G03F	007/029	X (abstract)
44		10142777	05/29/98	Japan		G03F	007/004	X (abstract)
YCT		10319581 A	12/04/98	Japan		G03F	007/004	X (abstract)
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)								
yct		Hinsberg et al., "Fundamental Studies of Airborne Chemical Contamination of Chemically Amplified Resists," Journal of Photopolymer Science and Technology, 6(4): 535-546 (1993).						
get	-	Houlihan et al., "A Study of Resist Outgassing as a Function of Differing Photadditives," <i>Proc. SPIE</i> , <b>3678</b> : 264-274 (1999).						
ycT		Uetani et al., "Positive ArF Resist with 2EAdMA/GBLMA Resin System," Proc. SPIE, 3678: 510-517 (1999).						
<i>J</i>								

**EXAMINER EXAMINER** 

Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.